

4/3/03

Substitute for form 1449A/PTO		Complete If Known		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)		Application Number	101631283	
		Filing Date	Concurrently Herewith	
		First Named Inventor	Cesar M. Garza et al.	
		Group Art Unit	1936	
		Examiner Name	Barnea	
Sheet		of	Attorney Docket Number	SC12879TP

U. S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number -Kind Code ² (if known)			
nm	AA	6,245,489 B1	06/12/2001	Baklanov et al.	430/43
nm	AB	US2003/0118935 A1	06/26/2003	Matsuzawa	430/270.1

FOREIGN PATENT DOCUMENTS							
Examine r Initials*	Cite No. ¹	Foreign Patent Document		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
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NON PATENT LITERATURE DOCUMENTS			
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nm	AC	Kudo et al., "CD Changes of 193nm Resist During SEM Measurement," <i>Advances in Resist Technology and Processing XVIII</i> , Francis M. Houlihan, Editor, <i>Proceedings of SPIE</i> , 2001, Vol. 4345, pp. 179-189.	
nm	AD	Vasconi et al., "193nm Metrology: facing severe e-beam/resist interaction phenomena," <i>Metrology, Inspection, and Process Control for Microlithography XV</i> , Neal T. Sullivan, Editor, <i>Proceedings of SPIE</i> , 2001, Vol. 4344, pp. 653-661.	
nm	AE	Wu et al., "Investigation on the Mechanism of the 193nm Resist Linewidth Reduction During the SEM Measurement," <i>Advances in Resist Technology and Processing XVIII</i> , Francis M. Houlihan, Editor, <i>Proceedings of SPIE</i> , 2001, Vol. 4345, pp. 190-199.	

Examiner Signature		Date Considered	8/24/05
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